

**【SP-06】**

## **Tendency of Lithography on the Various Self-Assembled Monolayer and Application of Patterned Surface**

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Self-assembled monolayer (SAM) has been widely used for good resist candidates in the Atomic Force Microscope (AFM) lithography.

One of methods to make the thin film is self-assembly process using various silane compound such as aminopropyltriethoxysilane(APS), octadecyltrichlorosilane(OTS), phenyltriethoxysilane(PTS).

In this presentation, patterned surface was fabricated through AFM lithography and studied the lithography tendency as to surface group effect.

also, it was explored the application of patterned surface to the array of liposome as well as immobilization of antibody.